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## APPLICANTS

Jae-eun Park, Yongin-city, KOREA, REPUBLIC OF;

Kang-soo Chu, Suwon-city, KOREA, REPUBLIC OF;  
Joo-won Lee, Suwon-city, KOREA, REPUBLIC OF; Jong-ho Yang, Seoul, KOREA, REPUBLIC OF;

## \*\* CONTINUING DATA \*\*\*\*\*

This application is a CIP of 10/459,943 06/12/2003

## \*\* FOREIGN APPLICATIONS \*\*\*\*\*

REPUBLIC OF KOREA 03-12324 02/27/2003  
REPUBLIC OF KOREA 04-7104 02/04/2004

## IF REQUIRED, FOREIGN FILING LICENSE GRANTED

\*\* 05/13/2004

Foreign Priority claimed	<input checked="" type="checkbox"/> yes <input type="checkbox"/> no	STATE OR COUNTRY KOREA, REPUBLIC OF	SHEETS	TOTAL CLAIMS	INDEPENDENT CLAIMS
35 USC 119 (a-d) conditions met	<input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after Allowance		DRAWING 6	54	3
Verified and Acknowledged	Examiner's Signature <i>TN</i> Initials				

## ADDRESS

Anthony P. Onello, Jr.  
 MILLS & ONELLO LLP  
 Suite 605  
 Eleven Beacon Street  
 Boston, MA  
 02108

## TITLE

Method for forming silicon dioxide film using siloxane

All Fees